

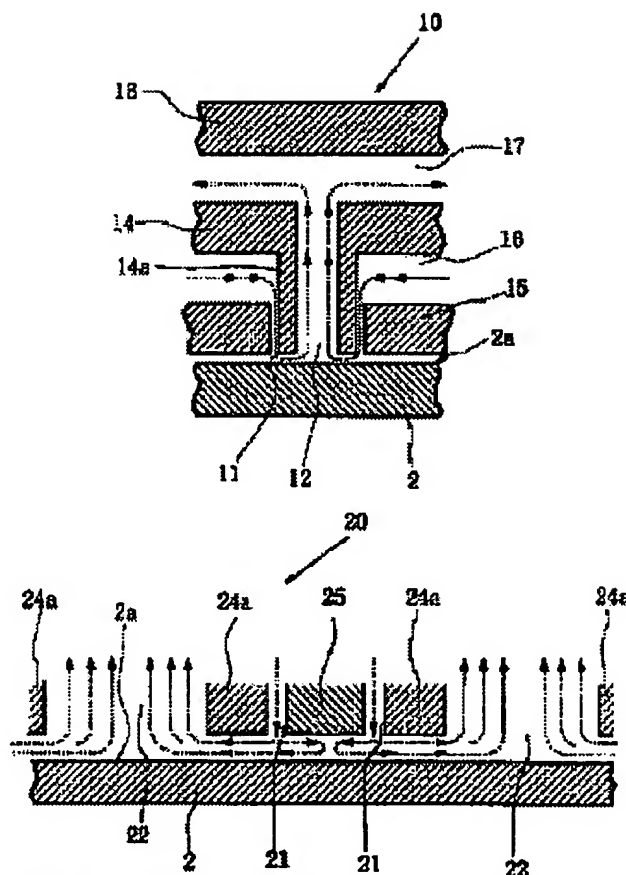
SEMICONDUCTOR SUBSTRATE CLEANING DEVICE

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Abstract of JP6260468

PURPOSE:To improve the cleaning solution utilizing efficiency of a semiconductor substrate cleaning device so as to improve the cleaning ability of the cleaning device by supplying a cleaning solution to the surface of a semiconductor substrate at a specific angle and recovering the cleaning solution through cleaning solution recovering ports provided near cleaning solution supplying ports.

CONSTITUTION:A plurality of cleaning solution supplying ports 11, 21,... is provided and a cleaning solution is supplied to the surface of a semiconductor substrate 2 at a substantial angle of 45-90 deg.. In addition, cleaning solution recovering ports 12, 22,... are provided near the ports 11, 21,... so as to recover the cleaning solution. The cleaning solution is sprayed upon the surface 2a to be cleaned of a semiconductor substrate 2 from, for example, the port 11 at an angle of 90 deg.. When the gap between the front end of a nozzle and the surface 2a is adjusted as an orifice, the flow rate and flow velocity of the cleaning solution can be adjusted. Therefore, fine solid particles adhering to the substrate 2 can be effectively removed.



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